

**ABSTRACT OF THE DISCLOSURE**

In a method of forming a micro pattern on a substrate, the micro pattern is predetermined to be formed in a first area of the substrate and not to be formed in a second area of the substrate spaced apart from the first area. A first shielding layer is formed on a surface of the substrate, and is configured to cover the second area and to expose the first area. A second shielding layer is formed on the surface of the substrate, is superimposed on the first shielding layer, and is configured to expose the first area of the substrate, and a portion of the first shielding layer. The first area of the substrate exposed from the second shielding layer is etched to form the micro pattern. The second shielding layer is then removed from the surface of the substrate and the first shielding layer. Finally, the first shielding layer is removed from the surface of the substrate.